

WEST**Freeform Search**

Database: US Patents Full-Text Database
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Derwent World Patents Index
IBM Technical Disclosure Bulletins

Term: 14 and (oxygen near3 plasma)

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USPT,PGPB	14 and (hydrogen near3 plasma)	12	<u>L7</u>
USPT,PGPB	14 and (oxygen near3 plasma)	34	<u>L6</u>
USPT,PGPB	14 and ((134/1.1 or 134/1.2).ccls.)	8	<u>L5</u>
USPT,PGPB	12 and 13	68	<u>L4</u>
USPT,PGPB	(clean\$3 or remov\$3) same (carbon near3 polymer or carbon near residue)	1742	<u>L3</u>
USPT,PGPB	11 same etch\$3	16415	<u>L2</u>
USPT,PGPB	photoresist near5 (pattern\$3 or open\$3)	23784	<u>L1</u>